

Exceptional service in the national interest



Electrodeposition and Electroless Deposition for Additive Manufacturing

David B. Robinson

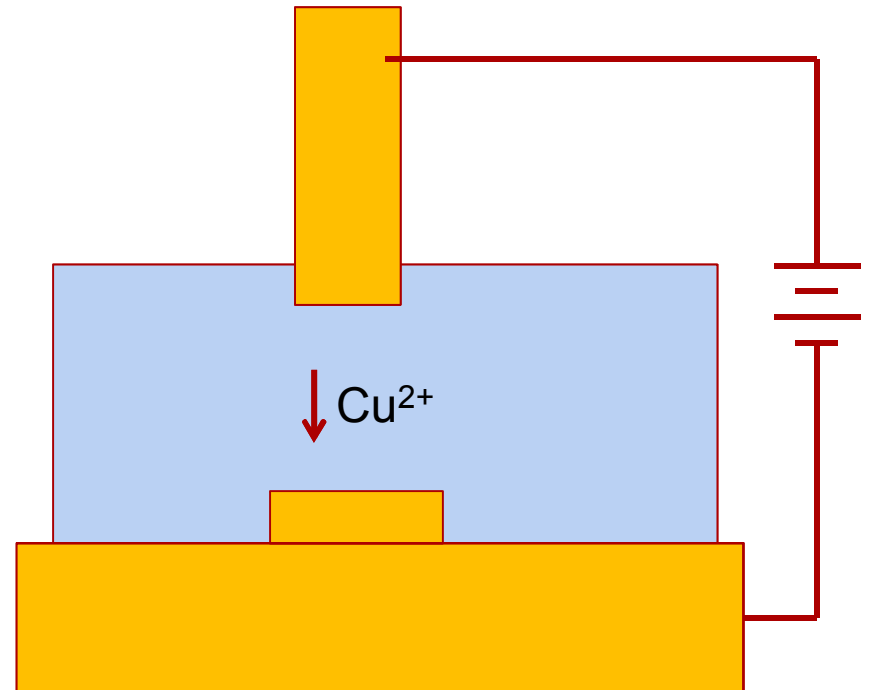
Sandia National Laboratories

Livermore, CA

August 2015

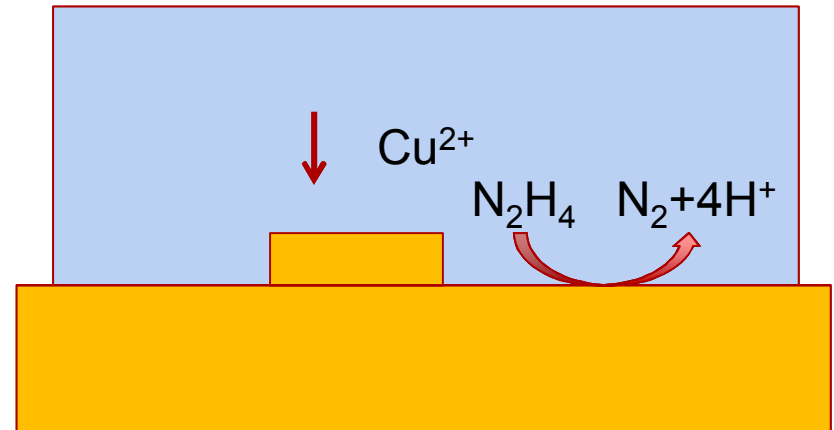
Electrodeposition

- Mixed electronic-ionic circuit
- Metal atoms become ions at sacrificial electrode
- Ions become metal atoms on part
- Electrons complete the circuit
- Ion concentration is low
- Ion transport is slow
- Challenge: spatial control



Electroless deposition

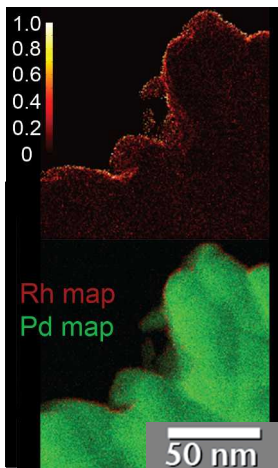
- Chemical reducing agent gives electrons to part
- Metal ions become atoms on part
- Charge balances in each phase
- Ion concentration is low
- Ion transport is slow
- Challenge: surface selectivity
- Challenge: spatial control
- Challenge: purity



Why?

- Spatial resolution: transcend scaling limits of laser sintering
- Dynamic range (part size : smallest feature size)
- Room temperature process
- No powder removal
- New ways to control microstructure
- New ways to control composition

nm scale



Capillino et al.,
Langmuir 30 4820 (2014)

70m electrodeposited,
post-processed aluminum



Wikipedia PD

cm scale

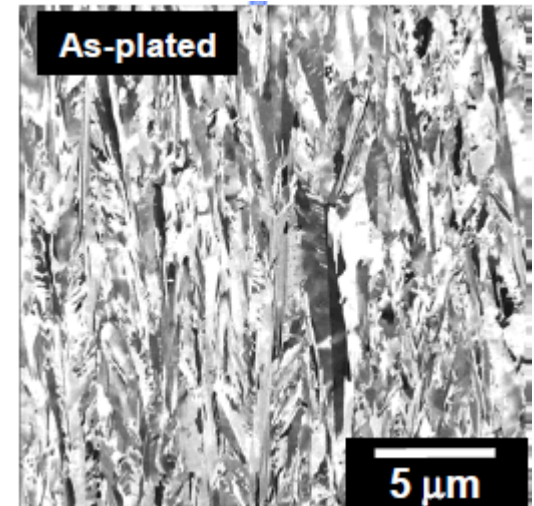
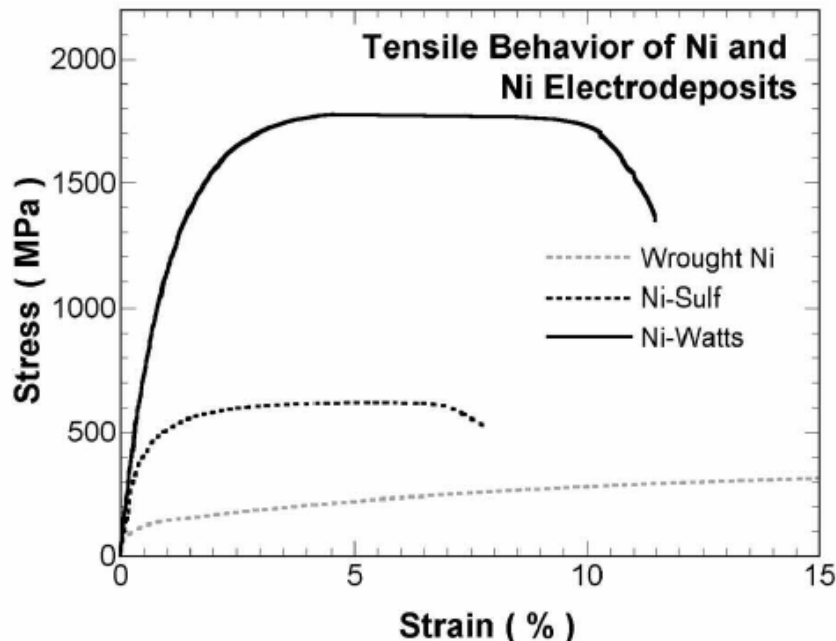
Laser sintered part

T. Ensz, SAND 2002-0574P

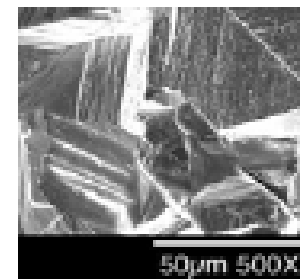


Materials

- Electrodeposition: Ni, Cu, Pd, Au, Fe, Co, Mn, Cr
 - Alloys; stainless steel
- Electroless: P or B impurities
- Multilayers
- Unique grain sizes, orientations



Ni + trace Mn



Ni
600 °C anneal

Strategies

- Scaling: large areas
- Plating rate: convection; jet electrodeposition
- Spatial selectivity: photoresist, laser assistance, convection
- 3D: layering; electroforming; stacking, folding post-process

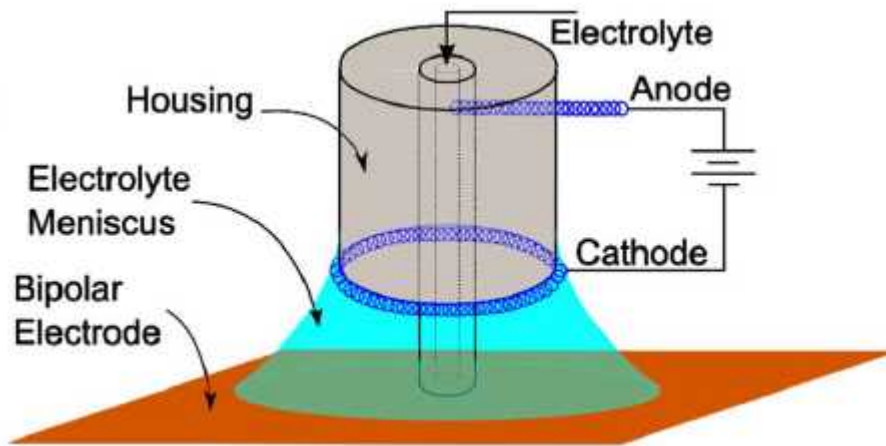


Wikipedia PD

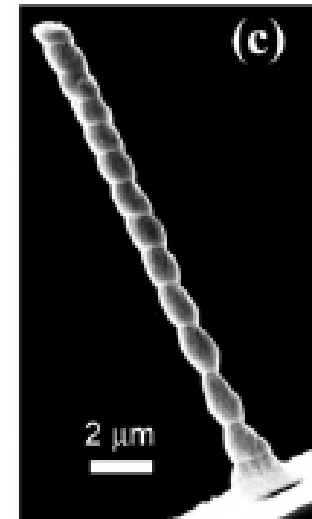
Other practical large-area, slow-growth technologies

Jet electrodeposition

- High convection, low conductivity: fast, local plating
- Large-area scalability is lost



Braun and Schwartz, J. Echem. Soc. 2015, 162, D180
Creative Commons



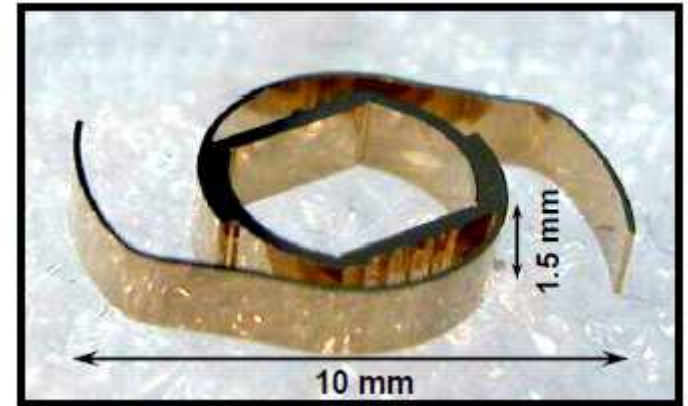
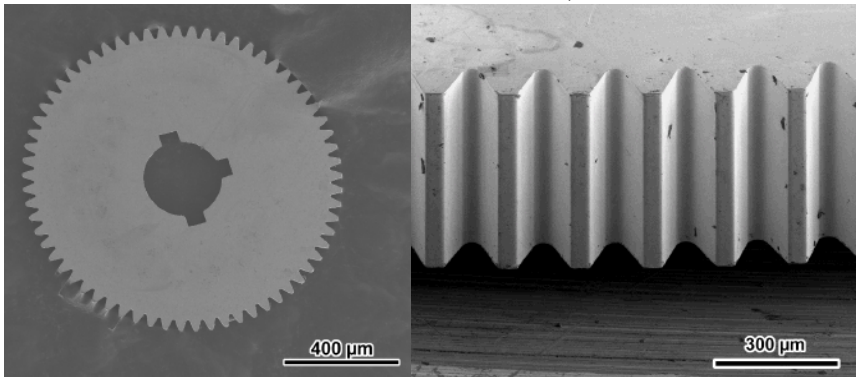
Suryavanshi and Yu
Nanotech. 2007, 18, 105305
Fig. 2 (IOP Journals)

Also Dover et al., SFF Symp. 1996; Sundaram et al., J. Manuf. Sci. Eng. 2015, 137, 021006-1

Deposition through photoresist

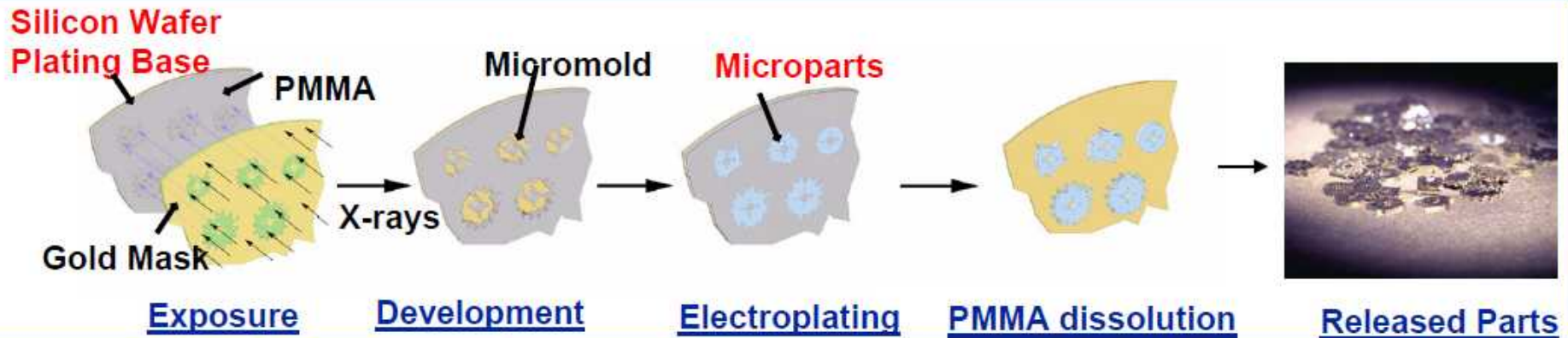
- LIGA
- UV LIGA

Prasad et al., SAND2000-1702

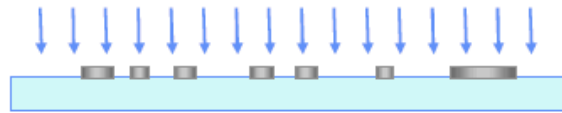


G. Kubiak, SAND2004-5590C

A. Morales, SAND2005-2039C



Deposition through photoresist



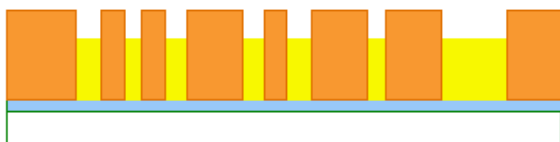
UV Photo Mask



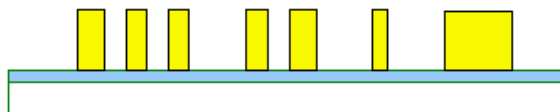
Photolithography



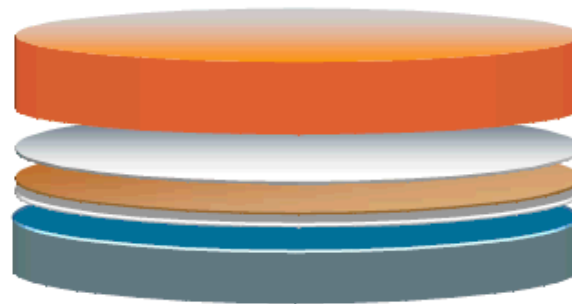
Development



Au Electroplating



Resist Removal

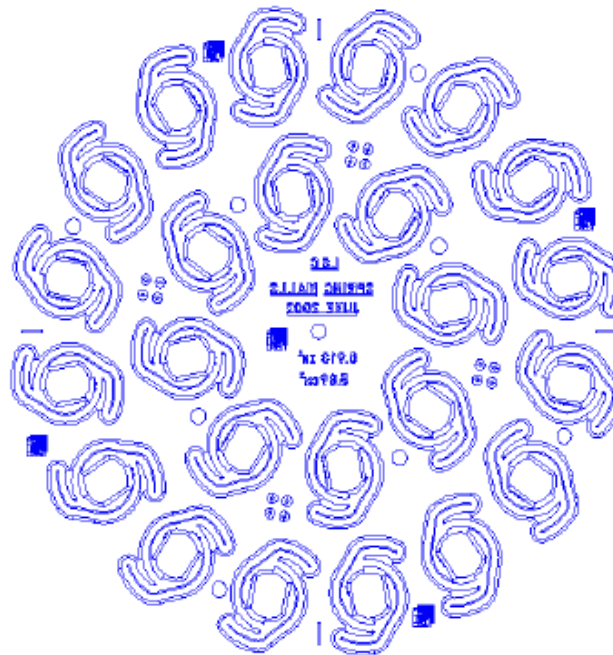


SU-8 Resist (DKS; 140 μm)

Adhesive Layer (0.75 μm)

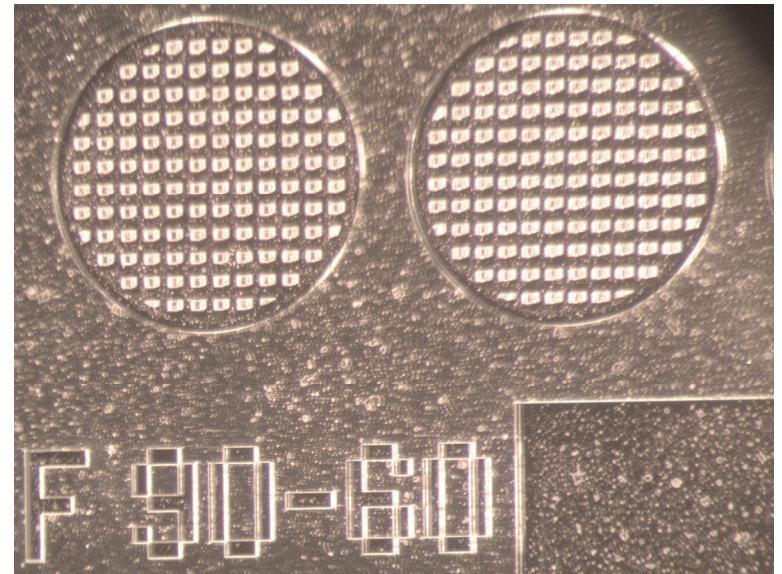
Ti/Cu/[Ti]; (100/1000/[100] Å)

Silicon (100 μm ; 75 mm)



Scalability

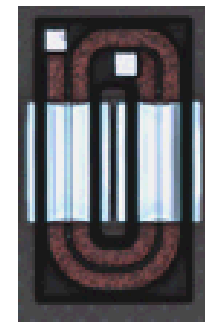
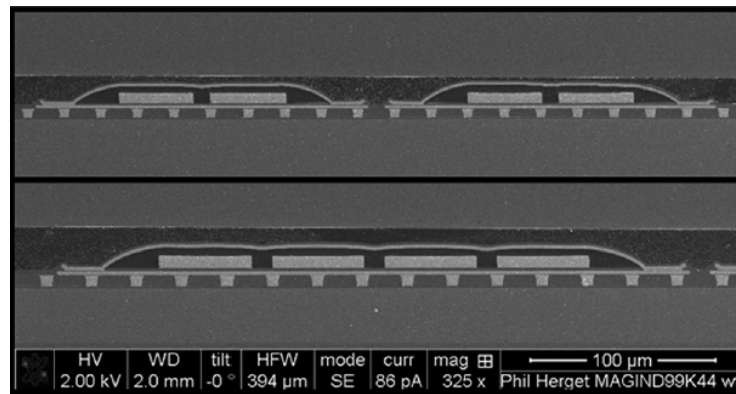
- Low-cost, large-area, stackable electroplated films
- Thick dry film UV photoresist (SUEX, DJDevCorp)
 - Printed circuit board technology applied to MEMS manufacturing
- Flexible electronics substrates (DuPont Pyralux Cu on polyimide)
- Plate, then release through Cu etch



C. Arrington, P. Finnegan, M. Bartsch, SNL, 2015

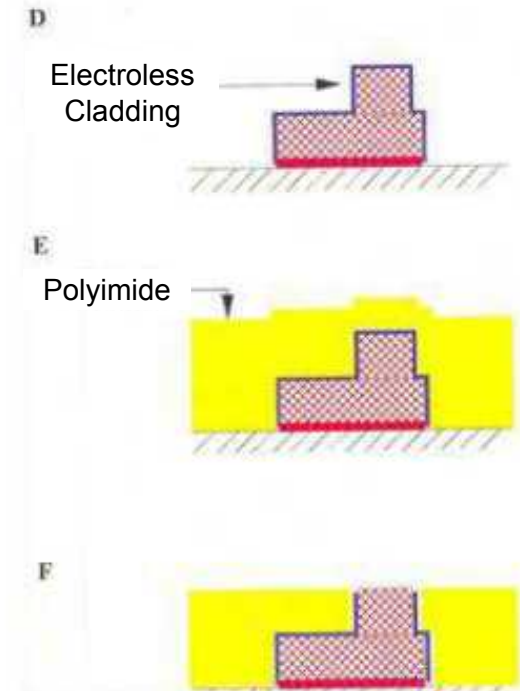
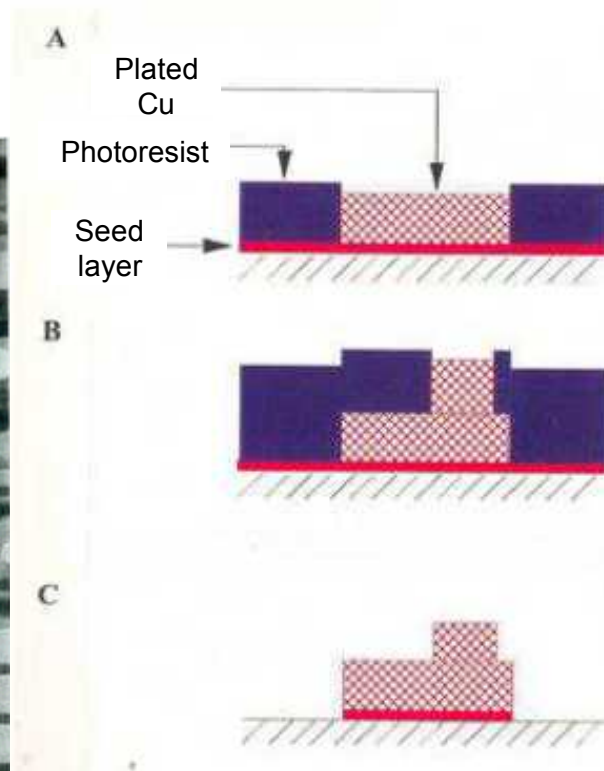
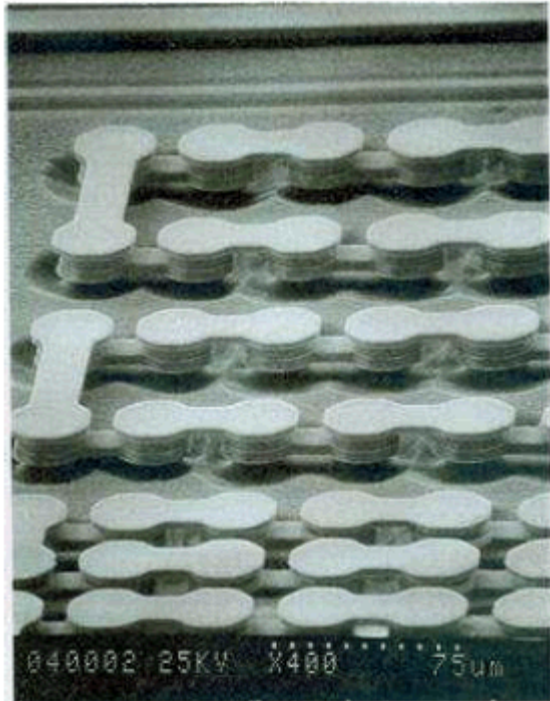
Multilayers

- IBM
 - Interconnects
 - HD write heads



Cu
Ni-Fe alloy

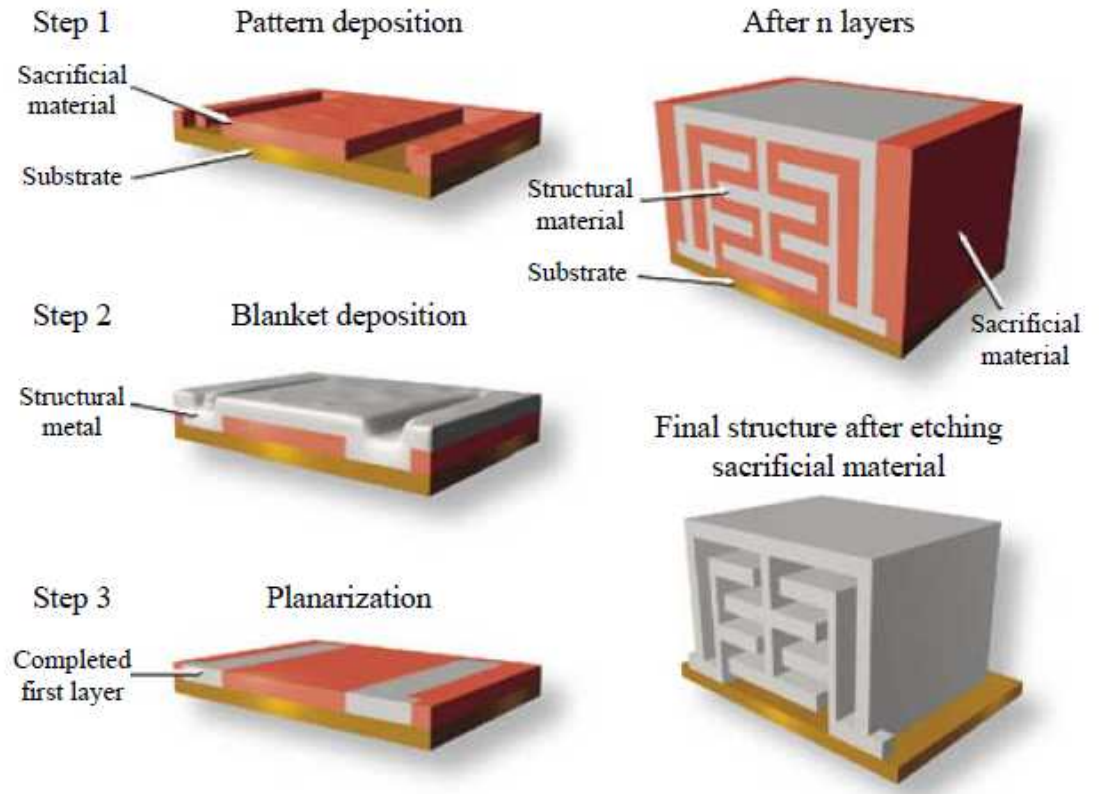
Wang et al., J. Appl. Phys. 2012, 111, 07E732
Copyright 2012, AIP Publishing LLC., reprinted with permission.



Krongelb and Romankiw, ECS Trans 2015, 64, 1.
Reproduced by permission of the Electrochemical Society.

Multilayers

- Microfabrica
 - Pd, Ni-Co alloy
 - Medical devices

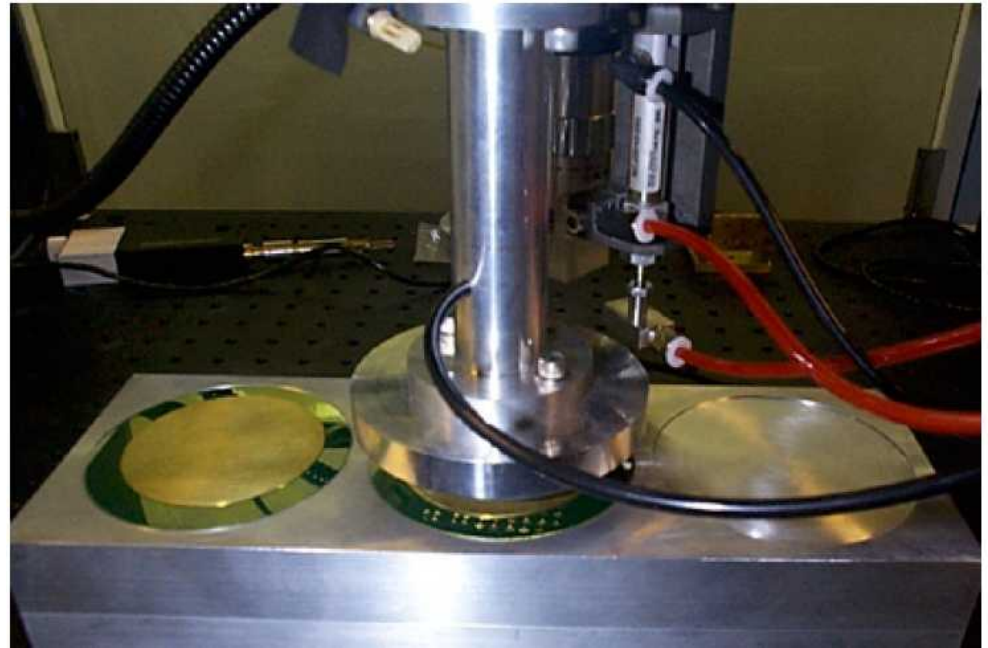
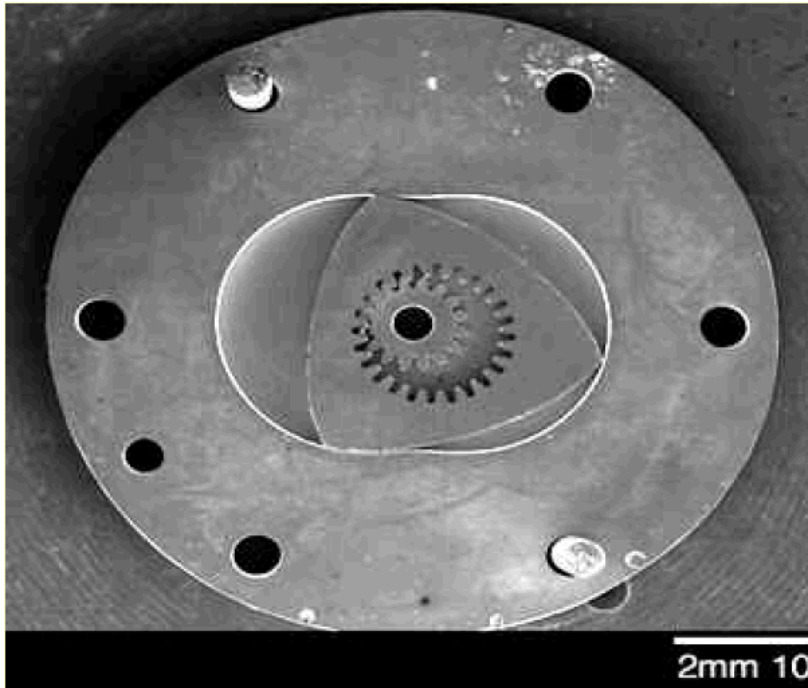


Cohen et al., Rapid Prototyping J., 2010, 16, 209
Reproduced by permission of Emerald Publishing.

Assembly

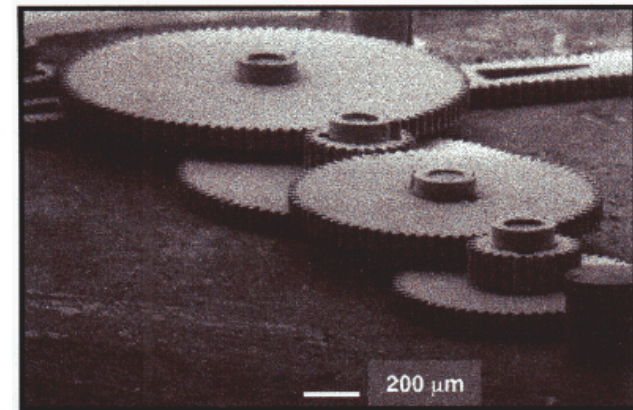
- Robotic tweezers
- Parallel stacking of parts
- Diffusion bonding

G. Kubiak, SAND2004-5590C



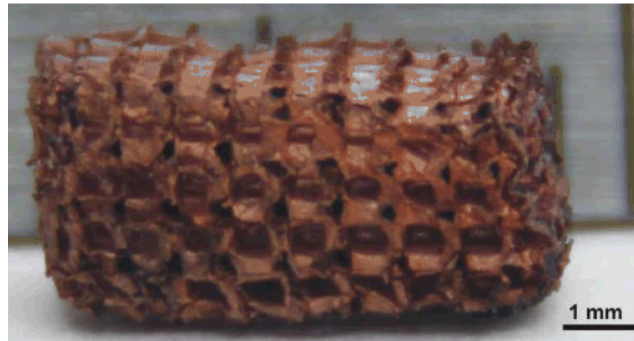
Feddema et al., SAND99-0746

Prasad and Christenson,
SAND2002-0536P



Electroforming

- 3D print plastic parts
- Chemical activation of plastic
 - Harsh chemicals such as chromic acid
 - Polymer functionalization
- Electroless deposition
- Further electrodeposition

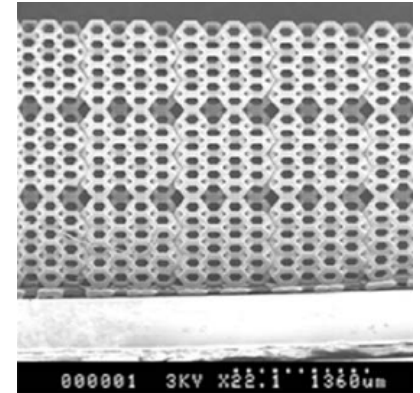
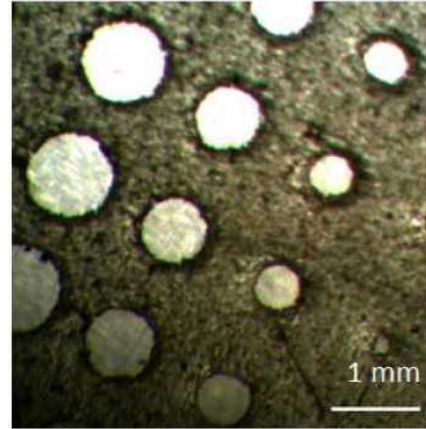
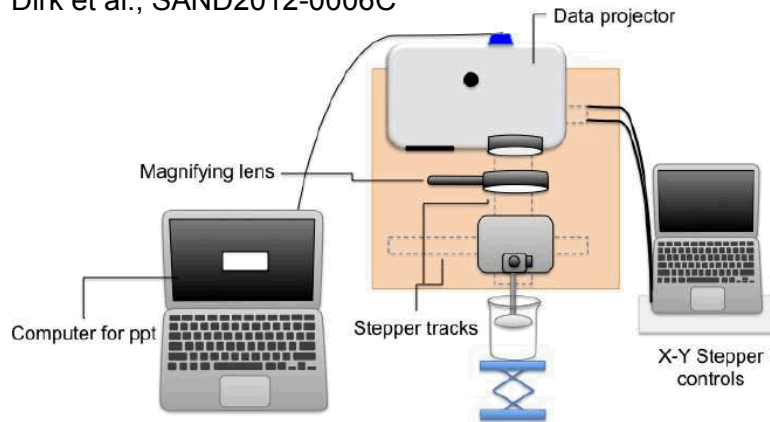


Wang et al.,
ACS Appl. Mater. Interf. 2014, 6, 2583.
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Electroforming

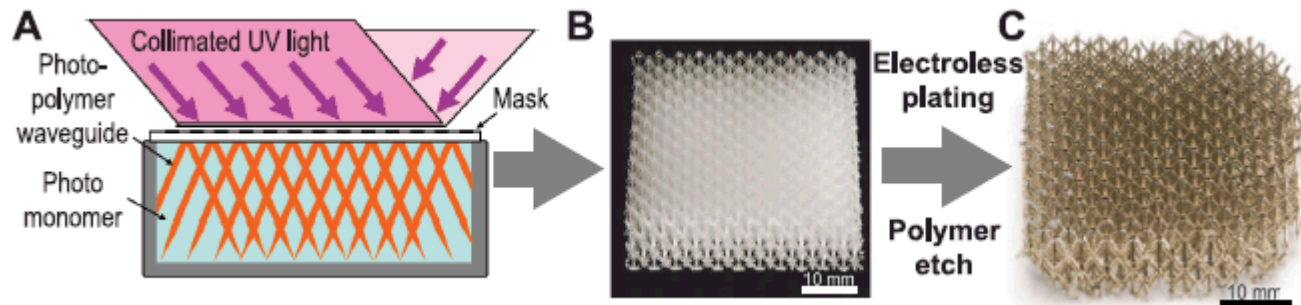
- Hughes, LLNL: metallization of sub-millimeter structures
- SNL: conducting polymers

Dirk et al., SAND2012-0006C



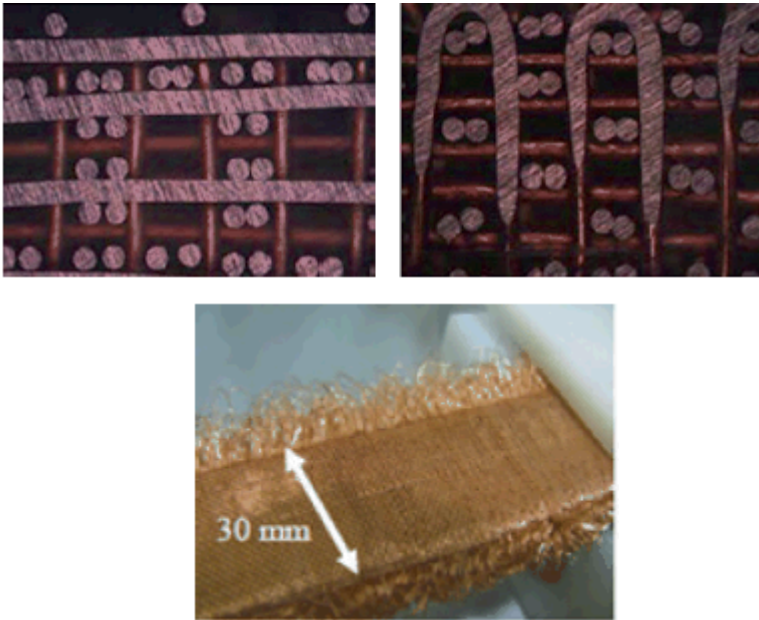
Zheng et al., Rev. Sci. Instr. 2012, 83, 125001
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From Schaedler et al., Science 2011, 334, 962.
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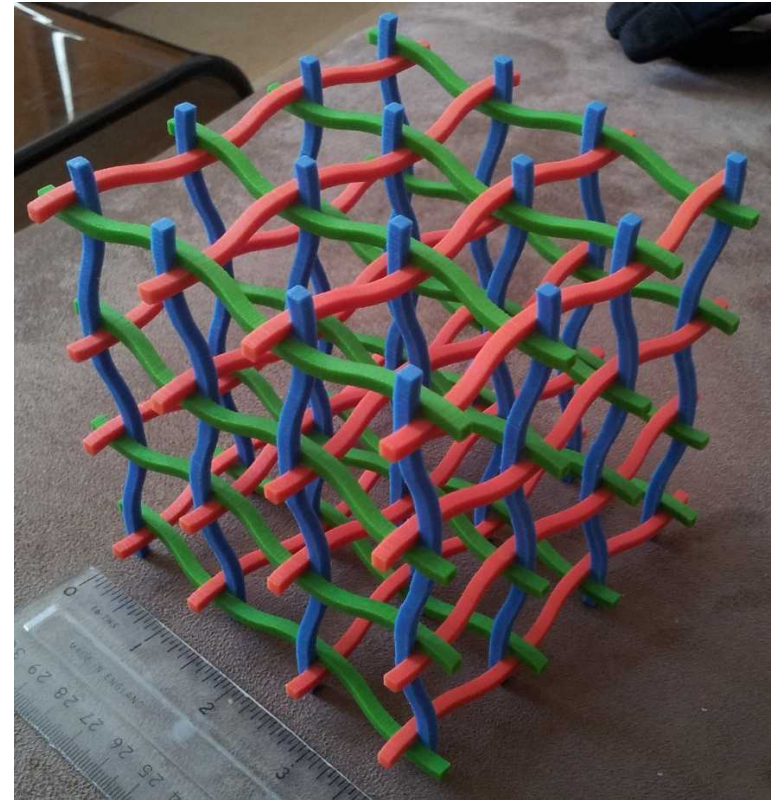


3D weaving

- 50 μm features, 100 mL-scale parts



Sharp et al., Procedia Mater. Sci. 2014, 4, 15
SAERTEX USA, Creative Commons



Derck van Schuylenburch, isoweave.com
US patent 5263516

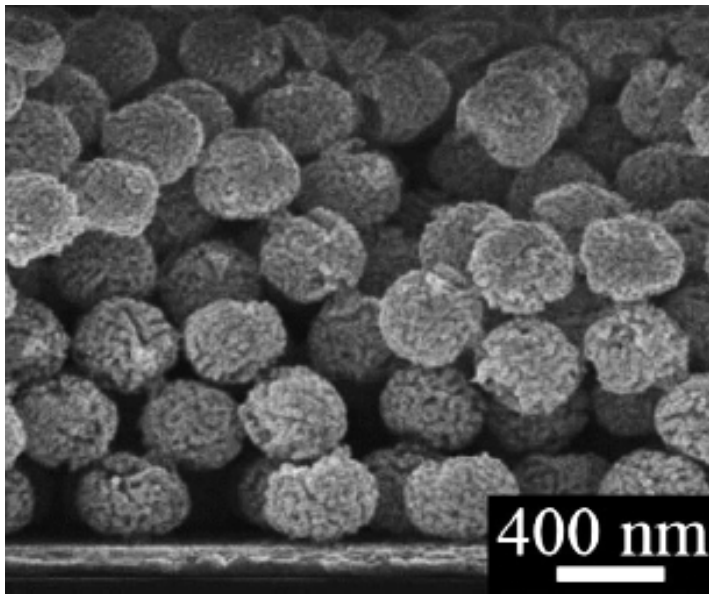
Synergy with metal powder sintering

- Electroforming
- Electropolishing
- Precise powder production

Electrochemical powder fabrication

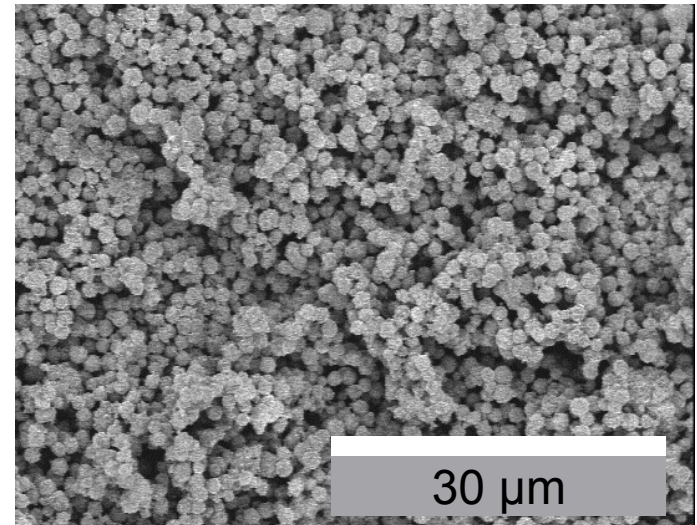
- Uniform, tunable particle size
- High surface energy for low-temperature sintering

Au powders by electrodeposition
Chae et al.,
ACS Appl. Mater. Interf. 4 3973 (2012)



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Electroless growth of
Cu and PdCu powders



Jones et al., Powder Tech. 267 95 (2014)

How electrochemistry fits in

- New length scale and material options
- Dimensions: x,y: good; z: bad
- Z strategies:
 - multilayer resists
 - inspection, stacking, bonding
 - 3D substrates
- Post processing
- Precise powder production